This listing of claims will replace all prior versions, and listings, of claims in the application:

Listing of Claims:

1. (Currently amended) A Compound Compounds of the general formula (I)

$$L \longrightarrow Cu \bigcirc O \bigcirc Cu \longrightarrow L$$
 (I)

in which copper is in the oxidation state +1, and

L is R-C≡C-R' having at least one silyl or ester group,

R'HC=CHR having at least one silyl or ester group,

 $R'_3Si-C\equiv C-R'$, R'_3N , $R'_2N(CH_2)_nNR'_2$, substituted or un-

substituted 2,2'-bipyridine, 1,10-phenanthroline, P(OR')₃,

P(alkyl)₃,

R'-O-R', R'-O(CH₂)_nO-R', R'-S-R', R'-S(CH₂)_nS-R', or a nitrile

from the group consisting of CH₃-C≡N, ^tBu-C≡N, C₄H₉C≡N

and or Ph-C≡N,

where

R is A, aryl, alkylaryl or alkynyl having at least one SiR'₃ or

COOR' group, and

R' is R, H, A, aryl, alkylaryl or alkynyl,

where L, R and R' may each, independently of one another,

adopt identical or different meanings in different positions of

the molecule,

and

A is straight-chain or branched C1-C30-alkyl, C3-C30-cycloalkyl,

straight-chain or branched C2-C30-alkenyl or straight-chain or

branched C3-C30-cycloalkenyl,

aryl is C6-C10-aryl or alkylaryl,

alkylaryl is C7-C18-alkylaryl,

alkynyl is straight-chain or branched C2-C30-alkynyl.

2. (Currenlty amended) A compound Compounds according to Claim 1, in which

A is straight-chain or branched C1-C9-alkyl, straight-chain or

branched C3-C9-cycloalkyl, straight-chain or branched C2-C9-

alkenyl or

straight-chain or branched C3-C9-cycloalkenyl,

aryl

is phenyl or naphthyl,

alkylaryl

is tolyl or mesityl,

alkynyl

is straight-chain or branched C2-C9-alkynyl,

and R and R' may each, independently of one another, adopt identical or different meanings in different positions of the molecule.

3. (Currently amended) A compound Compounds according to Claim 1, in which

A is straight-chain or branched C1-C4-alkyl from the group consisting of methyl, ethyl, n- and i-propyl and n-, i- and- tert-butyl, C3-C6-eycloalkyl from the group-consisting of cyclopropyl, cyclobutyl, cyclopentyl, and cyclohexyl, straight-chain-or-branched C2-C6-alkenyl from the group consisting of vinyl C2-C6-alkenyl, propenyl, butenyl, pentenyl, and hexenyl, or C3-C6-cycloalkenyl from the group consisting of cyclopropenyl, cyclobutenyl, cyclopentenyl, cyclopentadienyl and-or-methylcyclopentadienyl,

aryl

is phenyl or naphthyl,

alkylaryl

is tolyl or mesityl,

alkynyl

is straight-chain or branched C2-C6-alkynyl from the group

eonsisting of ethynyl, propynyl, butynyl, pentynyl and or hexynyl,

and R and R' may each, independently of one another, adopt identical or different meanings in different positions of the molecule.

4. (Currenlty amended) A compound Compounds according to Claim 1, in which L is R-C≡C-R' or R'HC=CHR, each having at least one silyl or ester group, and the radicals R and R` are as defined in Claim 1.

- (Currenlty amended) A compound Compounds according to Claim 1, in which L is R'₃Si-C≡C-R', where R' is SiMe₃, CH₃, C₂H₅, C₃H₇, C₄H₉, phenyl, COOMe or COOEt.
- 6. (Currenlty amended) A compound Compounds according to Claim 1, in which L is an alkyne selected from the group consisting of Me₃SiC≡C-SiMe₃, Me₃Si-C≡C-ⁿBu, McOOC-C≡C-COOMe, EtOOC-C≡C-COOEt and or Me₃Si-C≡C-R', in which R' is CH₃, C₂H₅, C₃H₇, phenyl, COOMe or COOEt.
- 7. (Currenlty amended) A compound Compounds according to Claim 1, in which L is an alkene selected from the group consisting of H₂C=CHSiMe₃, H₂C=CHCOOCH₃, H₂C=CHCOOC₂H₅ and or H₂C=CHSiR'₃, in which R', independently of one another, is CH₃, C₂H₅, C₃H₇, C₄H₉, HC=CH₂ or phenyl.
- 8. (Currenlty amended) <u>A compound Compounds</u> according to Claim 1, in which L is a <u>compound selected from the group consisting of</u> CH₃-C≡N, ¹Bu C≡N, C₄H₉C≡N, Ph-C≡N; N(CH₃)₃, N(C₂H₅)₃, H₂N (CH₂)₂ NH₂(CH₃)₂N(CH₂)₂-N(CH₃)₂, (C₂H₅)₂N(CH₂)₂N(C₂H₅)₂, H₂N-(CH₂)₄-NH₂, (CH₃)₂N-(CH₂)₄-N(CH₃)₂, (C₂H₅)₂N(CH₂)₄N(C₂H₅)₂, 2,9-dimethyl-1,10-phenanthroline; P(OCH₃)₃, P(OC₂H₅)₃, P(C₃H₇)₃, P(C₄H₉)₃, P(OC₆H₁₁)₃, P(OPh)₃; P(CH₃)₃, P(C₂H₅)₃, P(C₃H₇)₃, P(C₄H₉)₃, P(C₆H₁₁)₃; C₂H₅-O-C₂H₅, CH₃-O-C₄H₉, CH₃O-(CH₂)₂-OCH₃, C₂H₅O-(CH₂)₂-OC₂H₅, CH₃-S-CH₃, C₂H₅-S-C₂H₅, C₃H₇-S-C₃H₇, Ph-S-Ph, CH₃S-(CH₂)₂-SCH₃, CH₃S-(CH₂)₂-SCH₃, C₂H₅S-(CH₂)₂-SC₂H₅-and-or PhS-(CH₂)₂-SPh.
- 9. (Currenlty amended) A compound Compounds of the general formula (I) di{[bis(trimethylsilyl)acetylene]copper(I)} oxalate,

di{[(trimethylsilyl)(n-butyl)acetylene]copper(I)} oxalate, di[(vinyl-t-butyldimethylsilane)copper(I)] oxalate, di[(vinyldiethylmethylsilane)copper(I)] oxalate.

- 10. (Currently Amended) A process Process for the preparation of the a compound compounds of the general formula (I) according to Claim 1, characterised in that comprising reacting Cu₂O is reacted with oxalic acid and a Lewis base L in an inert solvent, and isolating the resultant product is isolated.
 - 11. (Currently Amended) A process Process according to Claim 10, wherein characterised in that an inert aprotic organic solvent is used which is an open-chain or cyclic aliphatic or aromatic hydrocarbon, a halogenated aliphatic or halogenated aromatic hydrocarbon or a linear or cyclic ether or a mixture of these hydrocarbons.
 - 12. (Currently Amended) A process Process according to Claim 10, characterised in that further comprising the utilizing a solvent which is selected from the group consisting of pentane, hexane, heptane, cyclohexane, toluene, methylene chloride, trichloromethane, chlorobenzene, diethyl ether and or tetrahydrofuran is used.
 - 13. (Currently Amended) A process Process according to Claim 10, characterised in that it is carried out under a protective-gas atmosphere.
 - 14. (Currently Amended) A process Process according to Claim 13, wherein characterised in that the protective gas employed is nitrogen or argon.
 - 15. (Currently Amended) A process Process according to Claim 10, wherein characterised in that the Lewis base L is employed in at least twice the stoichiometric ratio excess relative to the stoichiometric ratio of the starting materials Cu₂O and oxalic acid [,] but at least in twice the stoichiometric

ratio.

- 16. (Currently Amended) A process Process according to Claim 10, wherein characterised in that the starting materials Cu₂O, oxalic acid and Lewis base L are employed in a stoichiometric ratio of from 1:1:2 to 1:1:4.
- 17. (Currently Amended) A process Process according to Claim 10, wherein eharacterised in that two different Lewis bases L are employed in identical molar amounts.
- 18. (Currently Amended) A process Process according to Claim 10, wherein characterised in that the reaction is carried out within a reaction time of from about 1 to 24 hours at a temperature in the range from about -30 to +100°C.
- 19. (Currently Amended) A process Process according to Claim 10, characterised in that it is carried out at room temperature.
- 20. (Currently Amended) A process Process according to Claim 10, wherein characterised in that, when the reaction is complete, insoluble constituents are separated off, and the reaction product is isolated from the solution and, if necessary, purified, or in that the reaction product is separated from the reaction mixture by extraction, isolated and, if necessary, purified.
- 21. (Currently Amended) A process Process according to Claim 10, wherein characterised in that insoluble constituents are separated off by filtration.
- 22. (Cancelled)
- 23. (Currently Amended) Process A process for the production of highly pure, thin metallic copper layers, characterised in that wherein compounds of the general

metallic copper layers, characterised in that wherein compounds of the general formula (I) according to Claim 1 are heated, causing elimination of the Lewis base L and deposition of metallic copper deposited through decarboxylation.

- 24. (Currently Amended) Process A process according to Claim 23, characterised in that wherein the elimination of the Lewis base L is carried out at a temperature in the range from about 50 to about 200°C, and the decarboxylation is completed at a temperature in the range from about 150 to 350°C with formation of metallic copper.
- 25. (Currently Amended) Process A process according to Claim 23, characterised in that wherein the Lewis base L eliminated is recycled and, re-employed in a process for preparing compounds of general formula (I) by reacting Cu₂O with oxalic acid and the Lewis base in an inert solvent and isolating the product, and then using the resultant compounds of general formula (I) are used for the production of highly pure, thin metallic copper layers.
- 26. (Cancelled)